

Thus, inventions as characterized in I-II are related because they are disclosed as being capable of use together.

Should the Examiner maintain her restriction requirement, Applicant traverses on the basis of the reasons above. Only in order to be responsive to the outstanding official action, Applicant would then elect claims 1, 3, 4 and cancel claim 2.

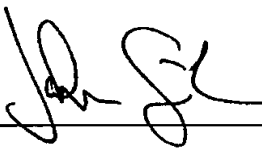
CONCLUSION

The Commissioner is authorized to charge any additional fees which may be required, including petition fees and extension of time fees, to Deposit Account No. 23-2415 (Docket No. 8003-370).

Respectfully submitted,

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Date: 5 April 2002



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In re Application of: Jae Heon Park

Serial No.: 09/624,712

Filed: July 25, 2000

For: Method for an Improved Developing Process in Wafer Photolithography

VERSION WITH MARKINGS TO SHOW CHANGES MADE

1 1. A method for sequencing a developer process to reduce wafer pattern defects,
2 comprising:
3 dispensing a substantially inert material onto a wafer surface prior to dispensing
4 developer fluid onto a surface of the substantially inert material.

1 2. A method for sequencing a developer process to reduce wafer pattern defects,
2 comprising:
3 inducing a flow of developer fluid across a portion of a wafer surface for a time
4 interval greater than a transit time for a fluid element to reach an outer wafer edge, the time interval
5 prior to [the] substantial completion of [the] a developing chemical reaction.